

## **REMARKS**

Reconsideration and allowance of this application are respectfully requested based on the following analysis.

### **1. Overview of Non-Final Office Action**

Claims 1-37 are pending in the application.

Claims 1-26 are withdrawn from consideration by Applicant's election without traverse in the reply filed on February 25, 2008.

Claims 27, 29-31, 34 and 35 are rejected under 35 U.S.C. § 103(a) as allegedly being unpatentable over Miyata (JP 2002/160366A) in view of Yasukawa et al. (US 2002/0140782; hereafter "Yasukawa").

Claim 28 is objected to as being dependent upon a rejected based claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

### **2. Analysis of Prior Art Rejection**

In rejecting claim 17 directed to a method of manufacturing a liquid jet head, the Examiner's position is, *inter alia*, that the Yasukawa reference teaches the following operation of the claimed method while Miyata fails to teach the same:

forming a protective film having resistance to liquid at least on an inner wall surface of the reservoir portion in the sealing plate.

Applicant respectfully traverses the Examiner's position.

The Examiner asserts that the film 90 (FIGS. 16-19) of Yasukawa corresponds to the claimed protective film formed on an inner wall surface of the reservoir portion in the sealing plate. However, the film 90 (which is a silicon dioxide film 92 in FIGS. 18-19) is only a mask film used in an etching process for forming the pressurizing chamber 82 (recess 97), the common ink chamber 84 (thorough hole 95) and the nozzle communicating hole 86 (thorough hole 99).

This mask film is merely termed a protective film 90 in Yasukawa, but is not formed on an inner wall surface of the reservoir portion of the sealing plate as claimed, because the plate or substrate, on which the film 90 is formed, is not the claimed sealing plate comprising a reservoir portion and a piezoelectric element holding portion. The claimed sealing plate may only be alleged to correspond to the frame 100 having the piezoelectric vibrating element (110) holding portion in FIG. 20 of Yasukawa. Accordingly, the substrate 91 of Yasukawa (FIGS. 18-19) on which the film 90 is formed on is not the claimed sealing plate. Thus, the film 90 of Yasukawa is completely different from the claimed protective film.

Therefore, the claimed inventions should not be rendered obvious over the cited references.

Claims 29-31, 34 and 35 should be allowable at least due to their dependencies and additionally recited elements therein.

### **3. Allowable Claim**

Applicant respectfully requests the Examiner to hold the rewriting of allowable claim 28 in abeyance until the arguments presented with respect to rejected claims have been reconsidered.

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In view of the above, reconsideration and allowance of this application are now believed to be in order, and such actions are hereby solicited. If any points remain in issue which the Examiner feels may be best resolved through a personal or telephone interview, the Examiner is kindly requested to contact the undersigned at the telephone number listed below.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,

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